**INFORMATION DISCLOSURE
STATEMENT BY APPLICANT**

(Use as many sheets as necessary)

Sheet 1 of 1

Complete if Known

Application Number	10/625,769
Filing Date	07/23/2003
First Named Inventor	Brian G. Hoover
Art Unit	3738
Examiner Name	CHATTOPADHYAY, U.
Attorney Docket Number	13621-43433

U. S. PATENT DOCUMENTS

Examiner Initials*	Cite No. ¹	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number-Kind Code ² (if known)			
MDV	1	US- 5061057	10/29/1991	KUMAKURA, Minoru, et al.	
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FOREIGN PATENT DOCUMENTS

Examiner Initials*	Cite No. ¹	Foreign Patent Document	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T ⁶
		Country Code ³ Number ⁴ Kind Code ⁵ (if known)				

Examiner
Signature

M. Vargst

Date

Considered

11/30/05

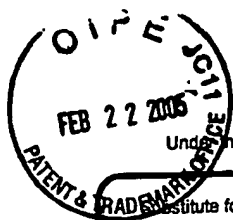
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NON PATENT LITERATURE DOCUMENTS				
Examiner Initials*	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.		T ²
WJV	A	WOLF, STANLEY PH.D. AND TAUBER, RICHARD N. PH.D., "SILICON PROCESSING FOR THE VLSI ERA, Volume 1: Process Technology," Book, 1st ed., Lattice Press (Sunset Beach, California), p. 430-437, (February 8, 1986).		
	B	ZIEGLER, J.F.; BIRSACK, J.P., LITTMARK, U., "THE STOPPING AND RANGE OF IONS IN SOLIDS," Book, Pergamon Press (U.S.A, U.K., Canada, Australia, Federal Republic of Germany), p. 109-110, 2, (February 8, 1985).		
	C	FERAIN, E.AND LEGRAS, R., "Track-etched membrane: dynamics of pore formation," Journal, Elsevier Science B.V. (North Holland), No. B84, p. 331-336, (February 8, 1994).		
	D	OKUYAMA, Y; HASHIMOTO, T.; KOGUCHI, T., "High Dose Ion Implantation into Photoresist," Journal, J. Electrochem. Soc. (Japan), Vol. 125 (No. 8), p. 1293-1298, (August 8, 1978).		
	E	VALIEV, K.A.; VELIKOV, L.V.; DUSHENKOV, S.D., "Pore formation in PMMA during x-ray exposure," Journal, Sov. Phys. Tech. Phys. (USSR), Vol. 32 (No. 7), p. 862-863, (February 8, 1988).		
	F	ORVEK, KEVI J.; HUFFMAN, CRAIG, "CARBONIZED LAYER FORMATION IN ION IMPLANTED PHOTORESIST MASKS," Journal, Elsevier Science Publishers BV (North Holland, Amsterdam), Vol. B (No. 7/8), p. 501-506, (February 8, 1985).		
	G	HICKS, C. et al., "Development and Clinical Assessment of an Artificial Cornea," Journal, Progress in Retinal and Eye Research, Elsevier Science Ltd. (Great Britain), Vol. 19 (No. 2), p 149-170 (2000).		
	H	TRAUTMAN, C., et al., "Etching threshold for ion tracks in polyimide," Journal, Nuclear Instruments and Methods in Physics Research B, Elsevier Science B.V. (North Holland, Amsterdam), Vol. B (No. 115), p. 429-433 (1996)		
	I	VIRK, H.S., et al., "Effects on insulators of swift-heavy-ion irradiation: ion-track technology," Journal, J. Phys. D: Appl. Phys., IOP Publishing Ltd. (UK), Vol. 31, p. 3139-3145, (1998).		
MDV	J	YASHAR, Alyson G., "Artificial iris device may reduce glare," Magazine, Opthamology Times, Advanstar Communications, Inc., (September 15, 2000)		

Examiner Signature	<i>M. Vargot</i>	Date Considered	11/30/05
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¹ Applicant's unique citation designation number (optional). ² Applicant is to place a check mark here if English language Translation is attached. This collection of information is required by 37 CFR 1.97 and 1.98. The information is required to obtain or retain a benefit by the public which is to file (and by the USPTO to process) an application. Confidentiality is governed by 35 U.S.C. 122 and 37 CFR 1.14. This collection is estimated to take 2 hours to complete, including gathering, preparing, and submitting the completed application form to the USPTO. Time will vary depending upon the individual case. Any comments on the amount of time you require to complete this form and/or suggestions for reducing this burden should be sent to the Chief Information Officer, U.S. Patent and Trademark Office, U.S. Department of Commerce, P.O. Box 1450, Alexandria, VA 22313-1450. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.